

MATERIALS RESEARCH SOCIETY
SYMPOSIUM PROCEEDINGS VOLUME 961

Nanostructured and Patterned Materials for Information Storage

November 27 – December 1, 2006
Boston, Massachusetts, USA

Printed from e-media with permission by:

Curran Associates, Inc.
57 Morehouse Lane
Red Hook, NY 12571
www.proceedings.com

ISBN: 978-1-60423-413-8

Some format issues inherent in the e-media version may also appear in this print version.

CAMBRIDGE UNIVERSITY PRESS
Cambridge, New York, Melbourne, Madrid, Cape Town,
Singapore, São Paulo, Delhi, Tokyo, Mexico City

Cambridge University Press
32 Avenue of the Americas, New York, NY 10013-2473, USA

www.cambridge.org

Materials Research Society
506 Keystone Drive, Warrendale, PA 15086
<http://www.mrs.org>

©Materials Research Society 2029

This publication is in copyright. Subject to statutory exception
and to the provisions of relevant collective licensing agreements,
no reproduction of any part may take place without the written
permission of Cambridge University Press.

First published 2029

CODEN: MRSPDH

ISBN: ; 9: /3/82645/635/:

Cambridge University Press has no responsibility for the persistence or
accuracy of URLs for external or third-part Internet Web sites referred to
in this publication and does not guarantee that any content on such Web sites
is, or will remain, accurate or appropriate.

Additional copies of this publication are available from:

Curran Associates, Inc.
57 Morehouse Lane
Red Hook, NY 12571 USA
Phone: 845-758-0400
Fax: 845-758-2634
Email: curran@proceedings.com
Web: www.proceedings.com

CURRAN ASSOCIATES INC.
proceedings
.com

TABLE OF CONTENTS

Novel Anionic Photoacid Generators (PAGs) and Photoresists for sub 50 nm Patterning by EUVL and EBL	1
<i>M. Wang, C. T. Lee, C. L. Henderson, W. Yueh, J. M. Roberts, K. E. Gonsalves</i>	
Photoimaging Materials Based on Base-Amplifying Silicone Resins Having Phenylsulfonylethyl Groups	8
<i>S. Inoue, K. Arimitsu, T. Gunji, Y. Abe, K. Ichimura</i>	
GMR in Excess of 10% at Room Temperature and Low Magnetic Fields in	14
<i>D. K. Pandya, P. Gupta, S. C. Kashyap, S. Chaudhary</i>	
Directed Self-Assembly of Thin Block Copolymer Films under Controlled Atmosphere	20
<i>S. Kim, R. M. Briber, A. Karim, R. L. Jones, H. C. Kim</i>	
Nanostructural Evolution in Non-Epitaxial Growth of Thin Films	26
<i>M. Hu, S. Noda, H. Komiyama</i>	
Quantum-Cross Tunneling Junction for High Density Memory	32
<i>H. Kaiju, K. Kondo, A. Ishibashi</i>	
Replication of Grating-Based Optically Variable Devices in Polypropylene	38
<i>P. W. Leech</i>	
Sequential Stretching Lithography	44
<i>H. Lin, O. V. Lima, L. Tan, Z. Li, J. Li</i>	
Nanoelectrode Lithography	50
<i>A. Yokoo, H. Namatsu, M. Oda</i>	
Tailoring Microdomain Orientation in Block Copolymer Thin Films for Lithographic Application	58
<i>H. Yoshida, H. Kitano, S. Akasaka, T. Inoue, M. Taknaka, H. Hasegawa, H. Nagano</i>	
Room-Temperature Nanoimprint Lithography	70
<i>K. I. Nakamatsu, S. Matsui</i>	
Template Fabrication Challenges for Patterned Media	85
<i>D. Resnick, G. Schmid, M. Miller, G. Doyle, C. Jones, D. Labrake</i>	
Fabrication of Tin Loaded Resorcinol Formaldehyde Aerogel Spheres for Extreme Ultraviolet Source Emission	95
<i>R. R. Paguio, A. Nikroo, C. A. Frederick, J. F. Hund, M. Thi</i>	
Formation and Characterization of Striped Nano-Channel Structure on the Functional Oxide Thin Film	102
<i>M. Kasahara, A. Matsuda, Y. Akita, W. Hara, K. Kobayashi, K. Kobayashi, T. Suzuki, M. Yoshimots</i>	
Impact of Planarization Sheet Addition on Full Wafer Printing Uniformity	107
<i>T. Leveder, S. Landis, L. Davoust, N. Chaix</i>	

Massively Parallel Scanning Probes Microscope with Digital Holographic Readout	113
<i>L. Sache, H. Bleuler</i>	
Memory Effects in Manganese Perovskites. Experiment and Theory	119
<i>N. Noginova, J. McClure, V. Gavrilenko, D. Novikov</i>	
Development of 3-D Magnetic Nano-Arrays by Electrodeposition into Mesoporous Silica Films	126
<i>J. Manning, R. Campbell, M. G. Bakker, X. Li, D. R. Lee, J. Wang</i>	
Fabrication of Magnetic Nanostructures for MRAM using Electron Beam and Focused Ion Beam Exposure of HSQ	132
<i>C. Chen, M. J. Cabral, R. Hull, L. R. Harriott</i>	
Measurement of Arrays of Dots Produced by Electron-Beam Lithography	149
<i>P. C. Hoyle, I. Laidler</i>	
A Nanodamascene Process to be used as a Building Block for Nanodevices	161
<i>C. Dubuc, J. Beauvais, D. Drouin</i>	
Application of Novel Base Amplifiers with 3-Nitropentan-2-yl Group to Photoreactive Materials	167
<i>K. Arimitsu, Y. Ito, T. Gunji, Y. Abe, K. Ichimura</i>	
Ab Initio Investigation of a CoFeB/MgO/CoFeB Interface	172
<i>H. S. Domingos, J. J. Martins</i>	
Nanoline Templating of Metals and the Underlying Surface Processes	177
<i>J. H. G. Owen, K. Miki</i>	
Process Integration of Composite High-k Tunneling Dielectric for Nanocrystal Based Carbon Nanotube Memory	183
<i>U. Ganguly, T. H. Hou, E. C. Kan</i>	
Nanofabrications for Information Technology	189
<i>K. Choi</i>	
Development of Block Co-Polymers as Self-Assembling Templates for Patterned Media	194
<i>V. Warke, M. L. Curry, M. G. Bakker, K. Hong, J. Mays, P. Britt, X. Li, J. Wang</i>	
Grain Size Refinement in Cu Bottom Lead in CPP GMR Stack	200
<i>Z. R. Tadisina, S. Gupta, C. Papusoi, H. Fujiwara, R. Morris, G. Thompson</i>	
Observation of Ge₂Sb₂Te₅ Thin Film Phase Transition Behavior According to the Number of Cycles Using Transmission Electron Microscope and Scanning Probe Microscope	206
<i>H. Kim, S. Choi, S. Kang, K. Oh, S. Kweon</i>	
Nonvolatile Two-Terminal Molecular Memory	213
<i>J. Snodgrass, G. Kennedy, W. N. Mei, R. Sabirianov</i>	
Supramolecular Self-Assemblies as High-Density Data-Storage Media	219
<i>N. Wintjes, M. Wahl, A. Kiebele, M. Stohr, S. Schintke, H. Spillman, H. J. Guntherodt, L. Gade, D. Bonifazi, F. Cheng, F. Diederich, T. Jung</i>	

Modeling Evaporation Driven Self-Assembly Systems for Magnetic Storage Arrays	224
<i>J. J. Dyreby, G. F. Nellis, K. T. Turner</i>	
Nanopatterning and Nanomachining with Table-Top Extreme Ultraviolet Lasers	230
<i>M. C. Marconi, P. W. Wachulak, M. G. Capeluto, G. Vaschenko, H. Bravo, C. S. Menoni, J. Rocca, E. H. Anderson, W. Chao, D. Attwood, O. Hemberg, B. Frazer, S. Bloom</i>	
Novel Methods to Reduce Pattern Size and Pitch for Data Storage Using Electron Beam Writing	236
<i>Z. Lu, A. N. Cartwright</i>	
Annealing Study of (Co/Pd) N Magnetic Multilayers for Applications in Bit-Patterned Magnetic Recording Media	242
<i>J. Rantschler, S. Zhang, T. R. Lee, D. Smith, D. Weller, S. Khizroev, D. Litvinov</i>	
Author Index	